

Supporting information for:

Rutile to Anatase phase transition induced by N doping in highly oriented TiO₂ films

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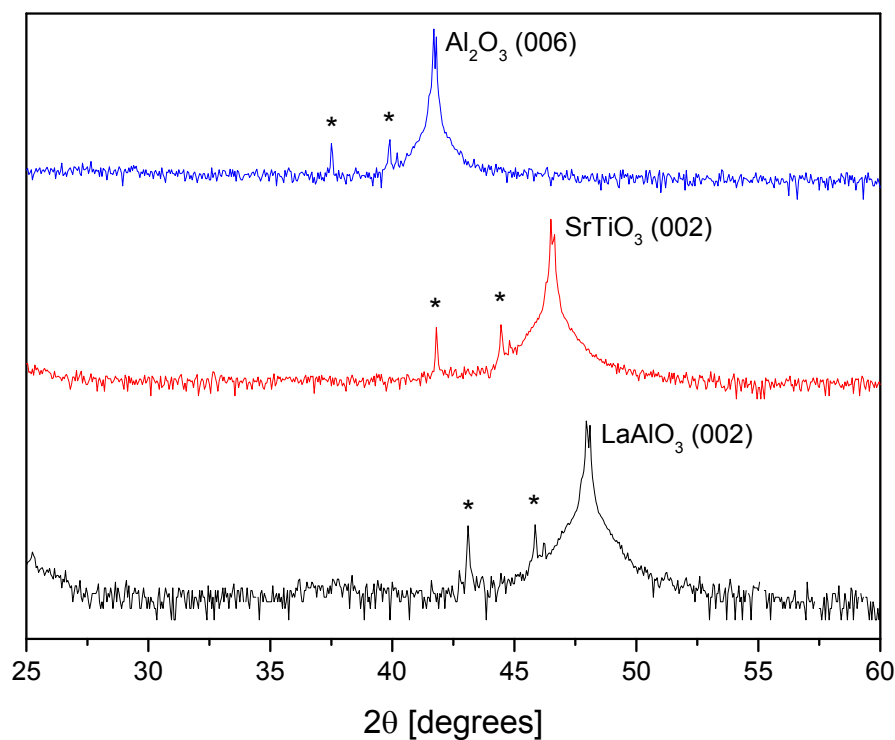


Figure S1. XRD patterns of uncoated substrates

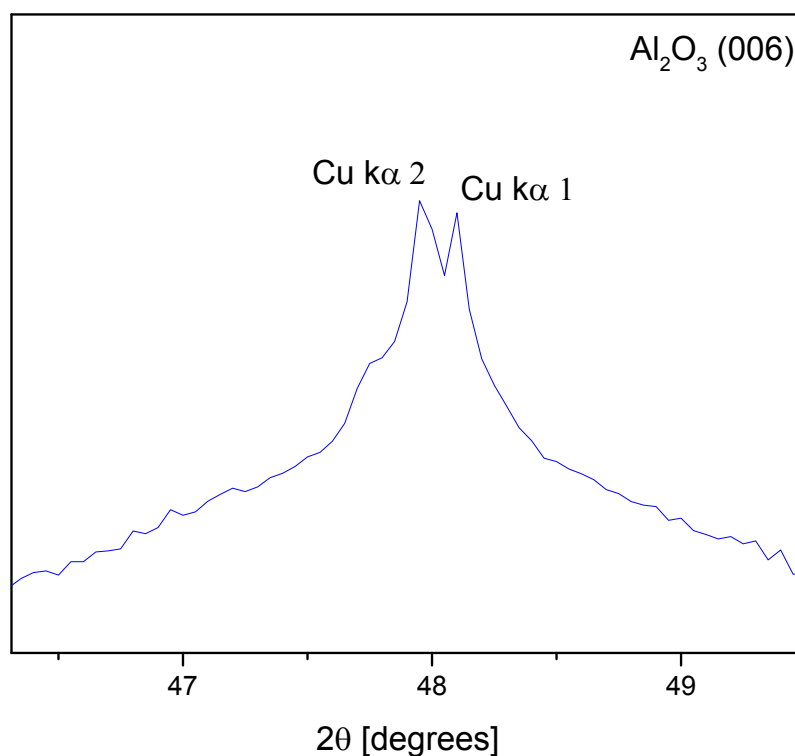


Figure S2. XRD of Al_2O_3 (006) showing splitting due to $K\alpha_1$ and $K\alpha_2$ wavelengths

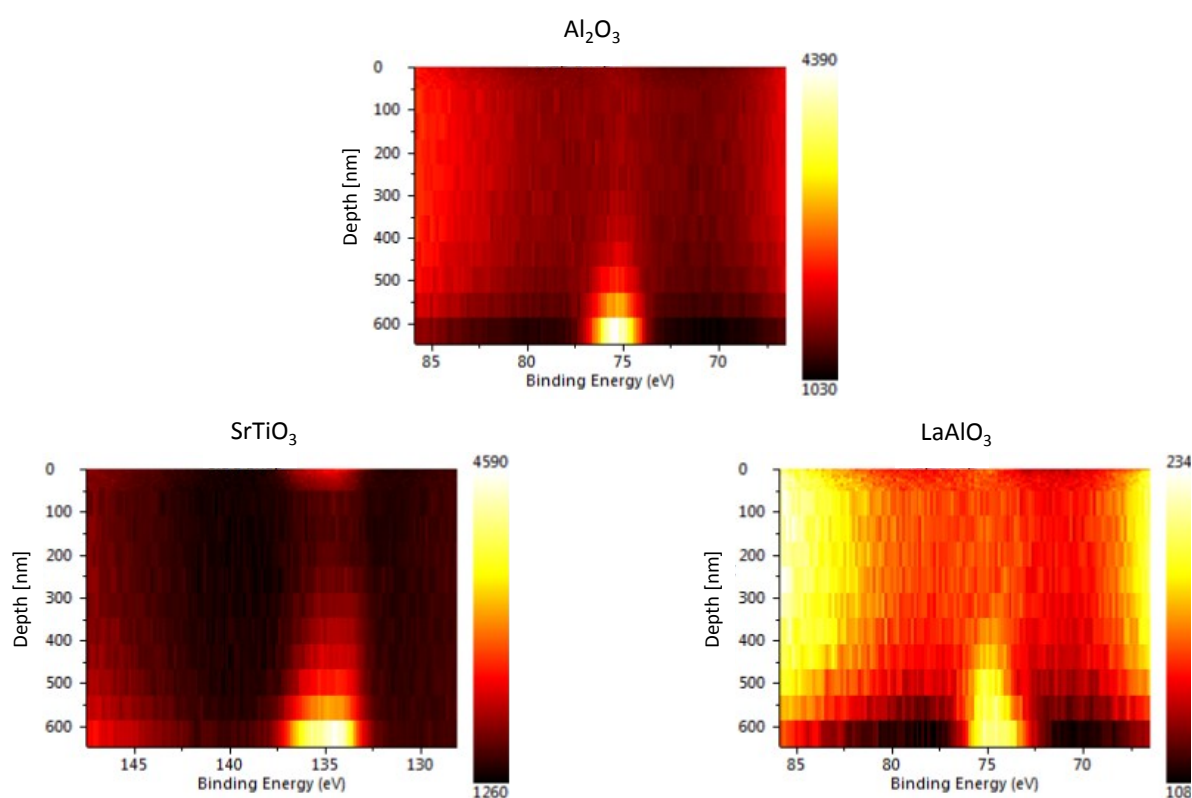


Figure S3. XPS depth profiles of TiO_2 films on Al_2O_3 , SrTiO_3 , and LaAlO_3 displayed as a heat map. For films grown on Al_2O_3 the Al 2p region is shown, for SrTiO_3 the Sr 3d region is shown, and for LaAlO_3 the Al 2p region is shown. These regions are used to identify the depth of the film-substrate interface and hence the thickness of the films.

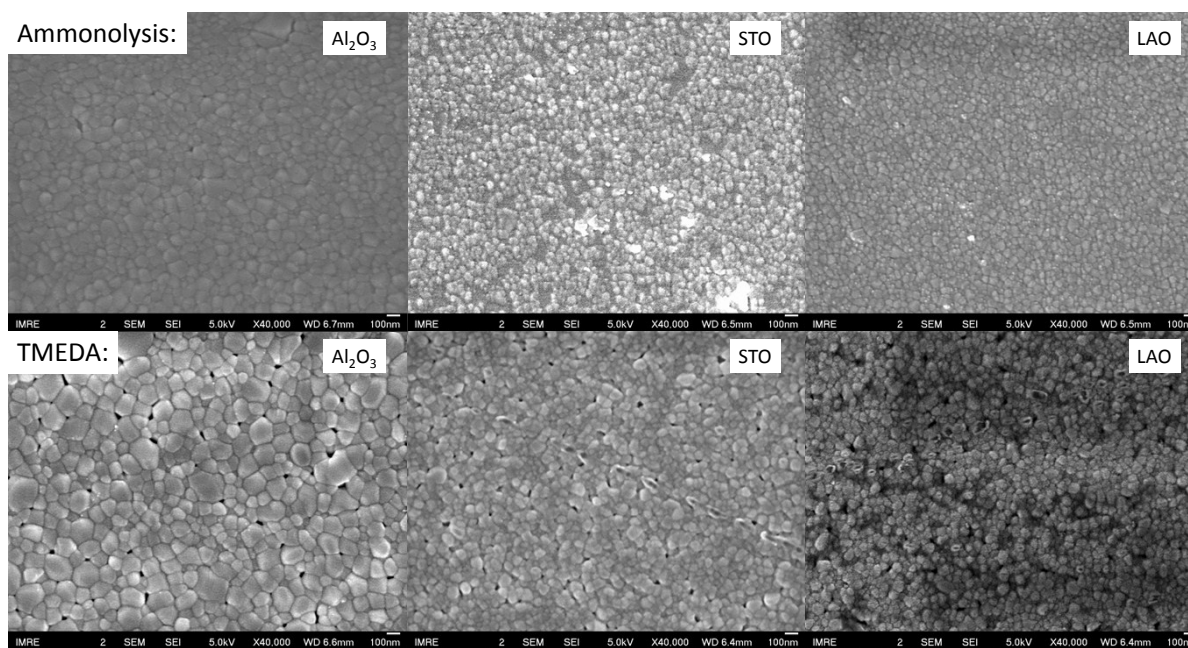


Figure S4. SEM images of nitrogen doped TiO₂ films (ammonolysis top, TMEDA bottom)